

Method for providing a process gas for a CVD reactor and related apparatus**Abstract**

The invention relates to an arrangement for supplying a process gas to a CVD reactor, comprising a first carrier gas supply line fed by a carrier gas source and having a first mass flow controller with a small flow range, and a second carrier gas supply line with a second mass flow controller having a large flow range, wherein the carrier gas supply line opens into an evaporation device for evaporating a solid or liquid starting material from which a process gas supply line to the CVD reactor originates, wherein a valve arrangement is arranged downstream of the second mass flow controller in the second carrier gas supply line having the second mass flow controller, which has an inlet and a first outlet flow-connected to the evaporation device and a second outlet flow-connected to a bypass line not opening into the evaporation device, wherein by switching the valve arrangement the carrier gas mass flow controlled by the second mass flow controller is selectively directed either through the evaporation device or around it, and a method for operating such an arrangement.

Figure 1